

Hybrid metrology approach for simultaneous characterisation of multiple properties at the nanoscale Fernando Castro

fernando.castro@npl.co.uk

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Agenda



- Challenges of metrology for nanomaterials
- Multiparameter metrology for nanotechnology
- Final comments

Nanomaterials - materials composed of one or more engineered components with at least one dimension between 1 nm and 100 nm.





2012 Angew. Chem. Int. Ed

fernando.castro@npl.co.uk

Complex nanomaterial applications require multiple characterisation methods



Ink-jet printed nanowire transistors



Structure-property relationship



Complex materials require multiple characterisation methods

Challenges of sequential nanoscale metrology

- Can I find the same exact position?
- Is my sample contaminated?

Powerful probes can damage/change delicate specimens





- Did I change my sample properties?
- Has my sample degraded?

Accurate measurement vs useful measurement NPL

Ultraviolet Photoelectron Spectroscopy on Oxide thin film

Photoluminescence on nanostructured polymer blend



Significant property changes during measurement

Even a fully calibrated, low uncertainty measurement does not guarantee dataset is useful for the sample manufacturer.





Can we develop methods that allow measurements of multiple properties simultaneously?

Scanning probe microscopy already does that



Photoconductive Atomic Force Microscopy





Does not provide chemical information

Nicholson and Castro, **Nanotechnology** 21 (2010) 492001 (review) Tsoi et al. **Energy Environ. Sci**., 4 (2011) 3646 Kim et al. **J. Mater. Chem**. C 3 (2015) 9224-9232





Kumar et al. under review 2016

Raman Spectroscopy





Tip-enhanced optical spectroscopy (Nanoscale Raman/Photoluminescence)







- Laser excites plasmon resonance
- Enhanced electromagnetic field close to the AFM tip

Nicholson and Castro, Nanotechnology **21** (2010) 492001 (review) Kumar et al. under review 2016

$$EF = \frac{(I_{Tip-in} - I_{Tip-out}) / A_{NF}}{I_{Tip-out} / A_{FF}}$$



Can we measure electrical performance, chemical and topographical information at the same time?



Possible issues that may affect reliability of data



Optimisation of focusing position



Avoid/minimise crosstalk



Excitation stability and spatial homogeneity



Tip degradation



Simultaneous Topography, Electrical, Optical Microscopy (STEOM)





Naresh et al, under review (2016)

Are probe depths similar?



The probe depths are determined by their dependence on the electric near-field intensity (E).

- Intensity of Raman signal is $\propto E^4$,
- Intensity of PL signal is ∞ *E*²η, where η is the PL quantum yield in the near-field

For small plasmonic enhancement of η , PL signal $\propto E^2$

Implication:

- Raman probes the top surface
- PL probes surface and subsurface

Nanoscale Photocurrent mapping

(Photoconductive atomic force microscopy)





Why do we see small areas with high photocurrent? Possible reasons

- Random currently fluctuations
- Measurement artefact (e.g. variation in contact resistance)
- Local compositional variation

Blakesley and Castro, Phys Rev B 2015 Kumar et al. 2016, submitted.

Simulated time evolution of photocurrent density in a homogeneous OPV film



Potential for performance improvement







Photocurrent

PV efficiency could be at least doubled if optimised donor-acceptor composition could be achieved

Inferred nanostructure of solar cell polymerfullerene blend





Final remarks



- Complex nanomaterials/devices require complementary characterisation methods
- Demonstration of simultaneous topography, electrical and optical microscopy (STEOM): allows direct correlation between chemical composition-topography-electrical performance
- New characterisation possibilities for organic, 2D and nanoelectronics



Unique capability Atmospheric control 3 optical axes

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Advanced Electronic Materials



Stability (in-situ characterisation)

Novel in-situ characterisation & accelerated tests





National Physical Laboratory

Standardisation

Measurement protocols International Round Robins



National Physical Laboratory

- Founded in 1900
- World-leading National Measurement Institute (Top 3 among ~100)
- 650 staff, 450 Graduate/PhD scientists multidisciplinary





Develop & disseminate UK's measurement standards, ensure they are internationally accepted

Multidisciplinary R&D and technical services for public and private sector Knowledge transfer, and advice between industry government and academia



 Even the best calibrated instrumentation, the lowest measurement uncertainty, when applied to a material that changes properties during the measurement, will give you the wrong result.

The measurement is correct but the result is meaningless!

Traditional metrology is expert in the measurement

End-user/customer is expert in the materials

There is a need for expertise bridging the gap between both worlds. That is Materials Metrology!

Include examples (photocurrent map or linearity of DSSCs, XPS/UPS of TCOs, others). Some changes in sample may be obvious (example of a film with a burned hole due to high power laser). Others are not easy to identify (xps example where the change is immediate during the measurement but fades away later on (transient effects).

Materials Metrology understands the interaction between sample and experiments in detail to ensure accurate and reliable methods provide customers with meaningful results.

